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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/764,751	01/26/2004	Leonard C. Pipes	ITL.0851D1US (P15016D)	8763
7590	03/25/2005		EXAMINER	
Trop, Pruner & Hu, P.C. Suite 100 8554 Katy Freeway Houston, TX 77024				ISAAC, STANETTA D
		ART UNIT		PAPER NUMBER
		2812		

DATE MAILED: 03/25/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary	Application No.	Applicant(s)
	10/764,751	PIPES ET AL.
	Examiner	Art Unit
	Stanetta D. Isaac	2812

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

1) Responsive to communication(s) filed on 25 February 2005.
 2a) This action is FINAL. 2b) This action is non-final.
 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

4) Claim(s) 22-27 is/are pending in the application.
 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
 5) Claim(s) _____ is/are allowed.
 6) Claim(s) 22-27 is/are rejected.
 7) Claim(s) _____ is/are objected to.
 8) Claim(s) _____ are subject to restriction and/or election requirement.

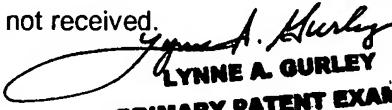
Application Papers

9) The specification is objected to by the Examiner.
 10) The drawing(s) filed on 24 January 2004 is/are: a) accepted or b) objected to by the Examiner.
 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
 Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 a) All b) Some * c) None of:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. _____.
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.


 LYNNE A. GURLEY
 PRIMARY PATENT EXAMINER
 TC 2800, AU 2812

Attachment(s)

1) Notice of References Cited (PTO-892)
 2) Notice of Draftsperson's Patent Drawing Review (PTO-948)
 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
 Paper No(s)/Mail Date _____

4) Interview Summary (PTO-413)
 Paper No(s)/Mail Date. _____
 5) Notice of Informal Patent Application (PTO-152)
 6) Other: _____

DETAILED ACTION

This Office Action is in response to the RCE and amendment filed on 2/25/05.

Currently, claims 22-27 are pending.

Continued Examination Under 37 CFR 1.114

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 2/25/05 has been entered.

Specification

The specification has not been checked to the extent necessary to determine the presence of all possible minor errors. Applicant's cooperation is requested in correcting any errors of which applicant may become aware in the specification.

Claim Rejections - 35 USC § 112

The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claims 22-27 recites the limitation "said substrate" in line 4. There is insufficient antecedent basis for this limitation in the claim. For examination purposes on the merits, the Examiner will interpret the limitation as "silicon substrate".

Claim Rejections - 35 USC § 102

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 22-27 are rejected under 35 U.S.C. 102(b) as being anticipated by Park US Patent 5,902,127.

Park discloses the semiconductor apparatus as claimed. See figures 1A-5B, with emphasis on figures 4A-4E, and corresponding text where Park teaches an apparatus comprising: a silicon substrate **40** (figure 4A; col. 4, lines 21-24); a barrier layer **44** over said silicon substrate (figure 4A; col. 4, lines 24-29); a trench **46** etched into said substrate through said barrier (figure 4A; col. 4, lines 29-33); a dielectric **48/50** in said trench (figures 4B-4C; col. 4, lines 34-47); and a plurality of ions implanted **Rp1** into said dielectric layer and said barrier layer, said substrate being substantially free of said ions (figure 4D; col. 4, lines 48-61).

Pertaining to claim 23, Park teaches the apparatus wherein the dielectric comprises silicon oxide (col. 4, lines 34-41).

Pertaining to claim 24, Park teaches the apparatus wherein said dielectric is damaged by said implanted ions (col. 4, lines 48-58, *Note*: the Examiner considers it to be inherent that the dielectric is damaged by the plurality of implanted ions, since the implanted ions are within in the oxide layers).

Pertaining to claim 25, Park teaches the apparatus wherein said barrier layer is formed on nitride (col. 4, lines 23-25).

Pertaining to claim 26, Park teaches the apparatus wherein said ions are selected from the group consisting of silicon, carbon, nitrogen, and oxygen (col. 4, lines 48-54, nitrogen).

Pertaining to claim 27, Park teaches the apparatus wherein the upper surface of said barrier layer and said dielectric are coplanar (col. 4, lines 62-67; col. 5, lines 1-8, *Note*: the Examiner takes the position that since the surface of the oxide layers are planarized using chemical mechanical polishing (CMP), and the barrier layer is later removed, it is inherent that the barrier layer and the dielectric are coplanar).

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Stanetta D. Isaac whose telephone number is 571-272-1671. The examiner can normally be reached on Monday-Friday 9:30am -6:30pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Lebentritt can be reached on 571-272-1873. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Stanetta Isaac
Patent Examiner
March 18, 2005



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